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Role of junction depth in light emission from silicon p-i-n LEDs

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INTEGRATION OF PHOTONICS ON CMOS PLATFORM









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Images: Ghent University - IMEC and IBM

Helsinki - ESSDERC 2011

HOW TO IMPROVE LIGHT EMISSION FROM SILICON?



Exploit carrier injection properties to fill the gap



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PREVIOUS WORK ON INJECTORS PROPERTIES



- DEV. I: reference (a) W_i = 100 µm
- DEV. II: reduced injector (b) $W_i = 10 \ \mu m$
- DEV. III: nano-size injector (c)





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ROLE OF JUNCTION DEPTH – EXPERIMENTAL MATERIAL

- Simple structure: lateral p-i-n diode
 Full CMOS compatibility
- High purity SOI substrates (~300 nm)
 Low SRH recombination
- All-around passivated surface
 Low surface recombination
- Ultra-shallow junctions
 (RP)CVD B or P



 $L = 100 \ \mu m$



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EXPERIMENTAL DATA: ELECTRICAL BEHAVIOR



Ultra-shallow junctions result in higher series resistance (lower current) Effect more pronounced on p⁺-i junction



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SPATIAL RESOLUTION OF LIGHT EMISSION



Light emission gradually decreases toward shallow junction side



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2D SIMULATIONS



Difference to ascribe to contact resistance



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SIMULATED RADIATIVE RECOMBINATION



Good agreement with experimental light emission



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EVIDENCE OF CURRENT CROWDING





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1D SANITY CHECK: NO VISIBLE EFFECT



CONCLUSIONS

Demonstrated role of junction depth in light emission (lateral p-i-n devices):

- Current crowding is proved to be detrimental to light emission
- 2D simulation as support
- Other possible effects ruled out via 1D simulation



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An example: the BrainGate[®] chip





REQUIREMENTS Non-toxic, reliable material and wireless connection between deep implant and the controller on the skull to avoid infections



Source: http://www.braingate.com/science.html UNIVERSITY OF TWENTE.

THINNED ACCESS SILICON LEDS

Contacts: carrier confinement

Field effect (gates)

Physical narrowing of the access

Potential barrier: band gap widening effect^[6]

- SRH: high quality substrates
- Surface: high quality and depletion via gate action
- Auger: low injection level regime





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PUSHING TOWARDS THE PHYSICAL LIMIT



EFFECT ON CARRIER VELOCITY: ELECTRONS





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